

| | Type | L # | Hits | Search Text | DBs |
|---|------|-----|------|--|-----------------|
| 1 | BRS | L1 | 8365 | scanning and exposure and (mask reticle) and wafer | USPAT; US-PGPUB |
| 2 | BRS | L2 | 2989 | 1 and photolithography | USPAT; US-PGPUB |
| 3 | BRS | L3 | 594 | 2 and @ad<19960930 | USPAT; US-PGPUB |
| 4 | BRS | L4 | 458 | 3 and optical | USPAT; US-PGPUB |
| 5 | BRS | L5 | 71 | 4 and titanium | USPAT; US-PGPUB |
| 6 | BRS | L6 | 15 | 5 and mirror | USPAT; US-PGPUB |